| L      | Hits  | Search Text   | DB  | Time stamp          |
|--------|-------|---|---|---------------------|
| Number | _     |   |   |                     |
| •      | 1     | 10/665412   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;            | 2004/07/30<br>13:24 |
| -      | 46291 | (resist or photoresist or photopolymer) with (Si! or silicon)   | IBM_TDB<br>USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT; | 2004/07/30<br>13:25 |
|        | 93664 | (resist or photoresist or \$6lithogr\$6) and (re\$work or rework or stripped ir stripping)  | IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;             | 2004/07/30<br>13:44 |
| -      | 10244 | ((resist or photoresist or photopolymer) with (Si! or silicon)) and ((resist or photoresist or \$6lithogr\$6) and (re\$work or rework or strip or stripped ir stripping))   | IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB     | 2004/07/30<br>13:28 |
| -      | 1133  | (((resist or photoresist or photopolymer) with (Si! or silicon)) and ((resist or photoresist or \$6lithogr\$6) and (re\$work or rework or strip or stripped ir stripping))) and (solvent same (THF or PGMEA or DMSO or ketones or esters or lactates))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2004/07/30<br>15:57 |
| -      | 85    | ((((resist or photoresist or photopolymer) with (Si! or silicon)) and ((resist or photoresist or \$6lithogr\$6) and (re\$work or rework or strip or stripped ir stripping))) and (solvent same (THF or PGMEA or DMSO or ketones or esters or lactates))) and ((re\$coat or coat) same (re\$expos\$4 or expos\$4)) | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2004/07/30<br>13:31 |
|        | 80443 | (resist or photoresist or \$6lithogr\$6) and ( strip or stripped or stripping)  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2004/07/30<br>15:19 |
| -      | 619   | ((resist or photoresist or \$6lithogr\$6) and (<br>strip or stripped or stripping)) and (re\$work<br>or rework)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2004/07/30<br>13:46 |
| -      | 39    | (((resist or photoresist or \$6lithogr\$6) and ( strip or stripped or stripping)) and (re\$work or rework )) and ((solvent or solution) same (THF or PGMEA or DMSO or ketones or esters or lactates))   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2004/07/30<br>16:40 |

|   | 1400 | 430/329   | USPAT;    | 2004/07/30 |
|---|------|---|-----------|------------|
|   |      |   | US-PGPUB; | 15:10      |
|   |      |   | EPO; JPO; | 13113      |
|   |      |   | DERWENT;  |            |
|   |      |   | IBM_TDB   |            |
| _ | 1    | 430/329 and (chemical\$3 near amplif\$9)  | USPAT;    | 2004/07/30 |
|   | _    | with (si or sily\$9 or silane or  | US-PGPUB; | 15:15      |
|   |      | \$9sesquioxane)   | 1         | 15:15      |
|   |      | 435esquioxaile)   | EPO; JPO; |            |
|   |      |   | DERWENT;  |            |
|   | 1    | 420/220 and //ahamicalt2 mass annulites   | IBM_TDB   | 0004/07/00 |
| _ | •    | 430/329 and ((chemical\$3 near amplif\$9)   | USPAT;    | 2004/07/30 |
|   |      | with (si or silo\$9 or silane or  | US-PGPUB; | 15:16      |
|   |      | \$9sesquioxane))  | EPO; JPO; |            |
|   |      |   | DERWENT;  |            |
|   |      |   | IBM_TDB   |            |
| • | 8    | 430/329 and ((chemical\$3 near amplif\$9)   | USPAT;    | 2004/07/30 |
|   |      | with (Si or silicon or ( silicon near (bearining                                      | US-PGPUB; | 15:53      |
|   |      | or containing))))   | EPO; JPO; |            |
|   |      |   | DERWENT;  |            |
|   |      |   | IBM_TDB   |            |
| • | 553  | 430/329 and (resist or photoresist or   | USPAT;    | 2004/07/30 |
|   |      | \$6lithogr\$6) and ( strip or stripped or   | US-PGPUB; | 15:47      |
|   |      | stripping)  | EPO; JPO; |            |
|   |      |   | DERWENT;  |            |
|   |      |   | IBM_TDB   |            |
| - | 27   | ( 430/329 and (resist or photoresist or   | USPAT;    | 2004/07/30 |
|   |      | \$6lithogr\$6) and ( strip or stripped or   | US-PGPUB; | 15:49      |
|   |      | stripping)) and (chemical\$3 near2 amplif\$8)   | EPO; JPO; |            |
|   |      | ,   | DERWENT;  |            |
|   |      |   | IBM_TDB   |            |
| • | 1127 | 430/329 and (resist or photoresist or   | USPAT;    | 2004/07/30 |
|   | İ    | \$6lithogr\$6) and ( strip or stripped or   | US-PGPUB; | 15:38      |
|   |      | stripping or stripper or remov\$4)  | EPO; JPO; | 10.00      |
|   |      | casppaig or easppor or rome (4.1)   | DERWENT;  |            |
|   |      |   | IBM_TDB   |            |
| _ | 68   | ( 430/329 and (resist or photoresist or   | USPAT;    | 2004/07/30 |
|   |      | \$6lithogr\$6) and ( strip or stripped or   | US-PGPUB; | 15:39      |
|   |      | stripping or stripper or remov\$4)) and   | EPO; JPO; | 10.55      |
|   |      | (chemical\$3 near2 amplif\$8)   | DERWENT;  |            |
|   |      | (Chemicaly3 hearz ampini30)   |           |            |
| _ | 41   | // 430/329 and /regist or photographs   | IBM_TDB   | 2004/07/20 |
| - | "    | (( 430/329 and (resist or photoresist or \$\\$6\ithogr\$6) and ( strip or stripped or | USPAT;    | 2004/07/30 |
|   |      |   | US-PGPUB; | 15:44      |
|   |      | stripping or stripper or remov\$4)) and   | EPO; JPO; |            |
|   |      | (chemical\$3 near2 amplif\$8)) not (( 430/329   | DERWENT;  |            |
|   |      | and (resist or photoresist or \$6lithogr\$6)  | IBM_TDB   |            |
|   |      | and ( strip or stripped or stripping)) and  |           |            |
|   | 4000 | (chemical\$3 near2 amplif\$8))  |           | 0004/00/20 |
| - | 4690 | (438/689,694).CCLS.   | USPAT;    | 2004/07/30 |
|   |      |   | US-PGPUB; | 15:44      |
|   |      |   | EPO; JPO; |            |
|   |      |   | DERWENT;  |            |
|   |      |   | IBM_TDB   |            |

| _ | 467   | ((438/689,694).CCLS.) and (resist or  | USPAT;                 | 2004/07/30 |
|---|-------|---|------------------------|------------|
|   |       | photoresist or \$6lithogr\$6) and ( strip\$5)   | US-PGPUB;<br>EPO; JPO; | 15:53      |
|   |       |   | DERWENT;               |            |
| - | 14    | ( ((438/689,694).CCLS.) and (resist or  | IBM_TDB<br>USPAT;      | 2004/07/30 |
|   |       | photoresist or \$6lithogr\$6) and ( strip\$5))  | US-PGPUB;              | 15:52      |
|   |       | and (chemical\$3 near2 amplif\$8)   | EPO; JPO;              |            |
|   |       |   | DERWENT;               |            |
|   | 2940  | (424/4 4 2 25) 001 0  | IBM_TDB                |            |
| - | 3810  | (134/1,1.3,26).CCLS.  | USPAT;<br>US-PGPUB;    | 2004/07/30 |
|   |       |   | EPO; JPO;              | 15:53      |
|   |       |   | DERWENT;               |            |
|   |       |   | IBM_TDB                |            |
| - | 365   | ((134/1,1.3,26).CCLS.) and (resist or   | USPAT;                 | 2004/07/30 |
|   |       | photoresist or \$6lithogr\$6) and ( strip\$5)   | US-PGPUB;              | 16:38      |
|   |       |   | EPO; JPO;              |            |
|   |       |   | DERWENT;               |            |
| - | o     | ( ((134/1,1.3,26).CCLS.) and (resist or   | USPAT;                 | 2004/07/30 |
|   |       | photoresist or \$6lithogr\$6) and ( strip\$5))  | US-PGPUB;              | 15:54      |
|   |       | and ((chemical\$3 near amplif\$9) with (Si or   | EPO; JPO;              |            |
|   |       | silicon or ( silicon near (bearining or   | DERWENT;               |            |
|   |       | containing))))  | IBM_TDB                |            |
| - | 396   | (resist or photoresist or photopolymer) with  | USPAT;                 | 2004/07/30 |
|   |       | ((chemical\$3 near amplif\$9) with (Si or<br>\$6sesquioxane or silane or \$6siloxane or | US-PGPUB;              | 16:36      |
|   |       | silicon or ( silicon near (bearining or   | EPO; JPO;<br>DERWENT;  |            |
|   |       | containing))))  | IBM_TDB                |            |
| - | 0     | ( ((134/1,1.3,26).CCLS.) and (resist or   | USPAT;                 | 2004/07/30 |
|   |       | photoresist or \$6lithogr\$6) and ( strip\$5))  | US-PGPUB;              | 15:56      |
|   |       | and ((resist or photoresist or photopolymer)  | EPO; JPO;              |            |
|   | :     | with ((chemical\$3 near amplif\$9) with (Si or  | DERWENT;               |            |
|   |       | \$6sesquioxane or silane or \$6siloxane or silicon or ( silicon near (bearining or      | IBM_TDB                |            |
|   |       | containing)))))   |                        |            |
| - | 62    | ( ((134/1,1.3,26).CCLS.) and (resist or   | USPAT;                 | 2004/07/30 |
|   |       | photoresist or \$6lithogr\$6) and ( strip\$5))  | US-PGPUB;              | 16:23      |
|   |       | and (solvent same (THF or PGMEA or DMSO   | EPO; JPO;              |            |
|   |       | or ketones or esters or lactates))  | DERWENT;               |            |
| _ | 742   | (regist or whaters into a shadow )  | IBM_TDB                |            |
| = | 142   | (resist or photoresist or photopolymer or (photo near sensitive)) and ((chemical\$3     | USPAT;<br>US-PGPUB;    | 2004/07/30 |
|   |       | near amplif\$9) same (Si or \$6sesquioxane  | EPO; JPO;              | 17:28      |
|   |       | or silane or \$6siloxane or silicon or ( silicon  | DERWENT;               |            |
|   |       | near (bearining or containing))))   | IBM_TDB                |            |
| - | 22653 | (resist or photoresist or photopolymer or   | USPAT;                 | 2004/07/30 |
|   |       | (photo near sensitive)) near6 strip\$5  | US-PGPUB;              | 17:18      |
|   |       |   | EPO; JPO;              |            |
|   |       |   | DERWENT;<br>IBM_TDB    |            |

| - | 364640 | ((solvent or solution or strip\$5) same (THF or PGMEA or pgme or DMSO or ketone or esters or lactate))   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2004/07/30<br>16:41 |
|---|--------|--|---|---------------------|
| • | 28     | ((resist or photoresist or photopolymer or (photo near sensitive)) and ((chemical\$3 near amplif\$9) same (Si or \$6sesquioxane or silane or \$6siloxane or silicon or ( silicon near (bearining or containing))))) and ((resist or photoresist or photopolymer or (photo near sensitive)) near6 strip\$5) and ( ((solvent or solution or strip\$5) same (THF or PGMEA or pgme or DMSO or ketone or esters or lactate))) | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2004/07/30<br>16:42 |
| - | 22     | hardened near photoresist  | IBM_TDB   | 2004/07/30<br>17:17 |
| - | 0      | ((resist or photoresist or photopolymer or (photo near sensitive)) and ((chemical\$3 near amplif\$9) same (Si or \$6sesquioxane or silane or \$6siloxane or silicon or ( silicon near (bearining or containing))))) and ( ((solvent or solution or strip\$5) same (THF or PGMEA or pgme or DMSO or ketone or esters or lactate)))  | IBM_TDB   | 2004/07/30<br>17:17 |
| - | 445    | (resist or photoresist or photopolymer or (photo near sensitive)) near6 (wet near strip\$5)  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2004/07/30<br>17:19 |
| - | 3      | ((resist or photoresist or photopolymer or<br>(photo near sensitive)) and ((chemical\$3<br>near amplif\$9) same (Si or \$6sesquioxane<br>or silane or \$6siloxane or silicon or ( silicon<br>near (bearining or containing))))) and ((resist<br>or photoresist or photopolymer or (photo<br>near sensitive)) near6 (wet near strip\$5))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2004/07/30<br>17:20 |
| - | 40     | ( ((solvent or solution or strip\$5) same (THF or PGMEA or pgme or DMSO or ketone or esters or lactate))) and ((resist or photoresist or photopolymer or (photo near sensitive)) near6 (wet near strip\$5))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2004/07/30<br>17:23 |